

RELIABILITY CHALLENGES FOR MEMS INTEGRATION



EDN 2003 Innovator/Innovation of the Year Award Winner for Components

STMicroelectronics LIS3L02 three-axis low-g accelerometer March 29, 2004

Milano, 28th November 2006

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Outline

- **MEMS Products:**
 - Technology Competition
 - Market Acceptance
- **MEMS Oxymoron**
- **MEMS ST approach to:**
 - Manufacturing Processes
 - Reliability Assessment Methodologies
- **Conclusions**



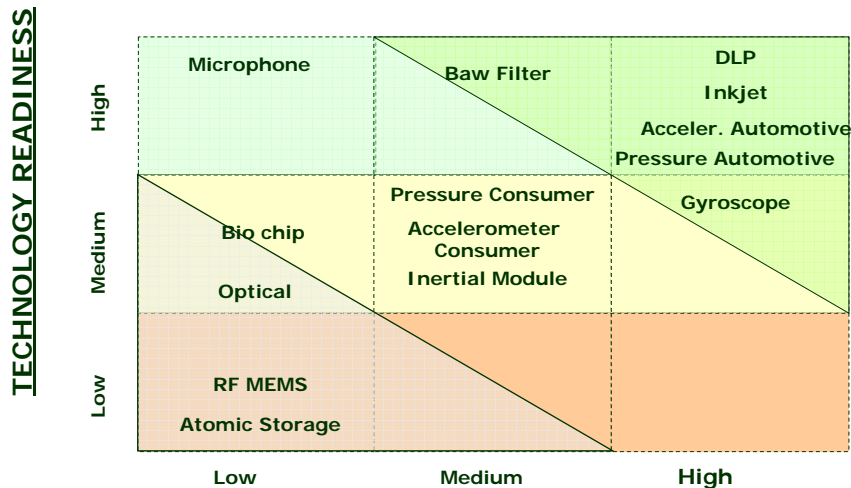


MEMS Competition in a Nutshell

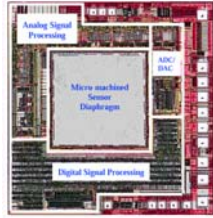
Mems family	Compete with	price	performances
ACCELEROMETER			
GYROSCOPE	QUARTZ/PIEZO	x	x
INERTIAL MODULE	HYBRID	x	x
BAW FILTER	SAW		x
PRESSURE			
BIO CHIP	HYBRID	x	x
ATOMIC STORAGE	ELECTRICAL MEMORY		x
RF MEMS	RADIO ARCHITECTURE		x
OPTICAL	OEO SOLUTIONS	x	x
INKJET			
DLP	LCD		x
MICROPHONE	ELECTRET		x



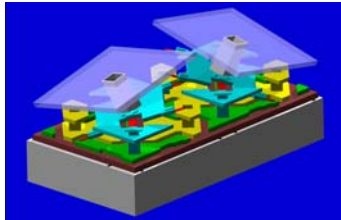
MEMS Market acceptance



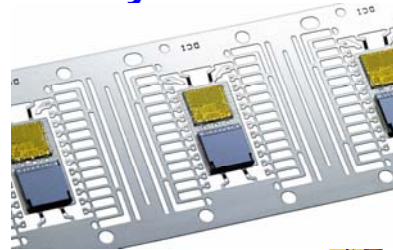
Most Successful Microsystems



Pressure Sensor



MicroMirror



Accelerometer



Printer Cartridges



IC and uMachining Technologies

Category	IC	Surface	THELMA	Wet Bulk	DRIE Bulk	VENSEN
Lithography	Stepper	Stepper	Stepper	Contact	Stepper or Contact	Stepper
Structural Material	N/A	CVD Poly	Epi Poly	Mono Si	Mono Si	Mono Si
Sacrificial Material	N/A	Si Oxide	Si Oxide	Si Substrate	Si Substrate	Mono Si
Cleanroom Class	1 - 10	10 - 100	10 - 100	100- 1000	100 - 1000	10 - 100
Wafer Diameter	8" - 12"	4" - 6"	4" - 6"	4" - 6"	4" - 6"	6" - 8"
Photo Levels (#)	> 20	> 20	6 ; 8	2 ; 6	6 ; 8	10
Min. Linewidth	< 0.13 um	1 um	2 um	6um	3 um	1 um



Many Different Materials can also be used!



MEMS Oxymoron

MEMS are built in Semiconductor fabs.....

.....but they are not CMOS.....

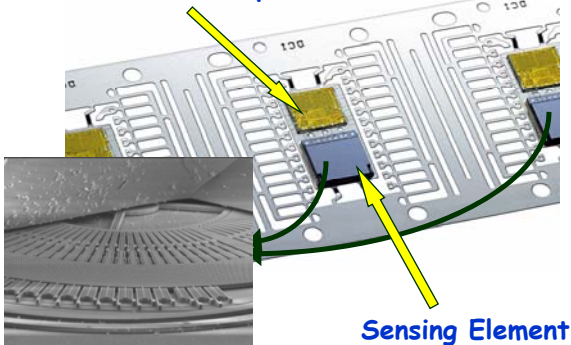
a common process platform across the industry is missing and perhaps will never exist.....

the MEMS silicon foundry is an oxymoron

ST MEMS Accelerometers

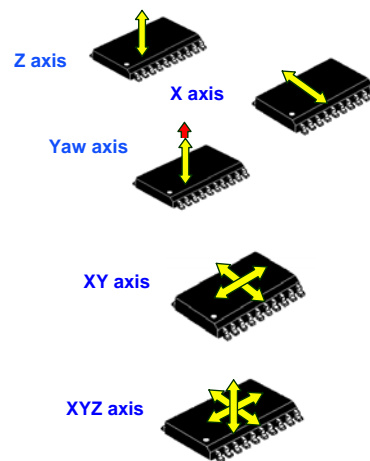
Hybrid Integration

Control IC and Capacitive I/f



THELMA15 Process

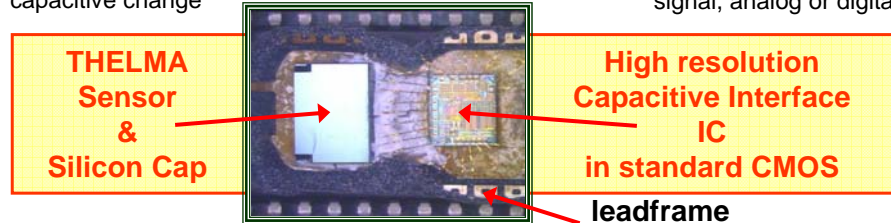
LIS Sensitive axis



Two Dice – Single Package Approach: System Considerations

MEMS sensor chip translates acceleration into a differential capacitive change

Interface IC chip translates small capacitance changes into output signal, analog or digital



- Performance optimization
- High modularity and flexibility
- Custom additional integration on interface IC
- Low cost solution (std plastic package)

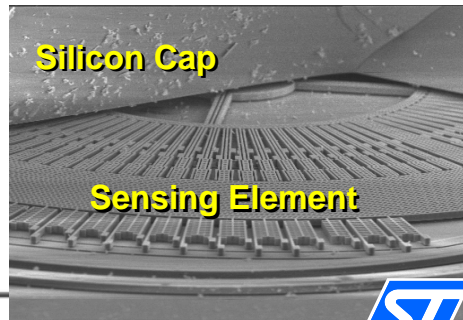
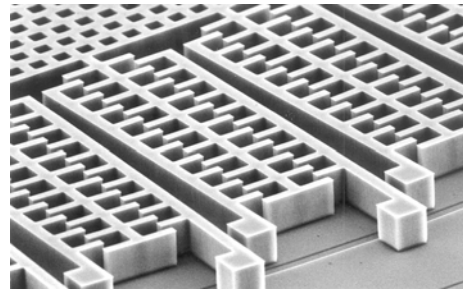
THELMA Process Highlights

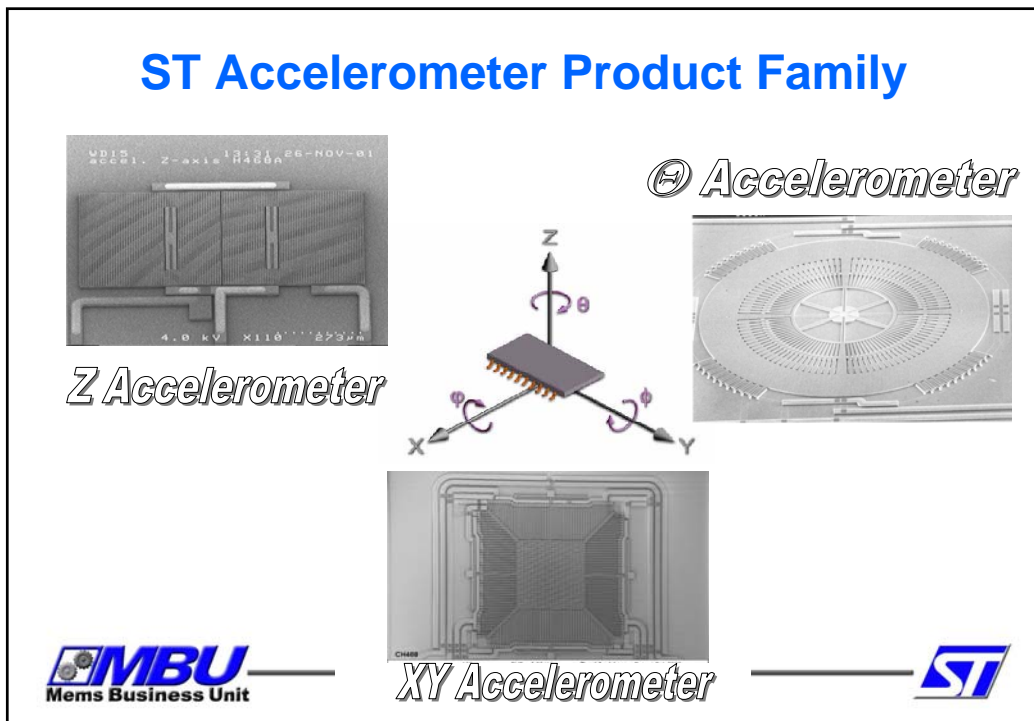
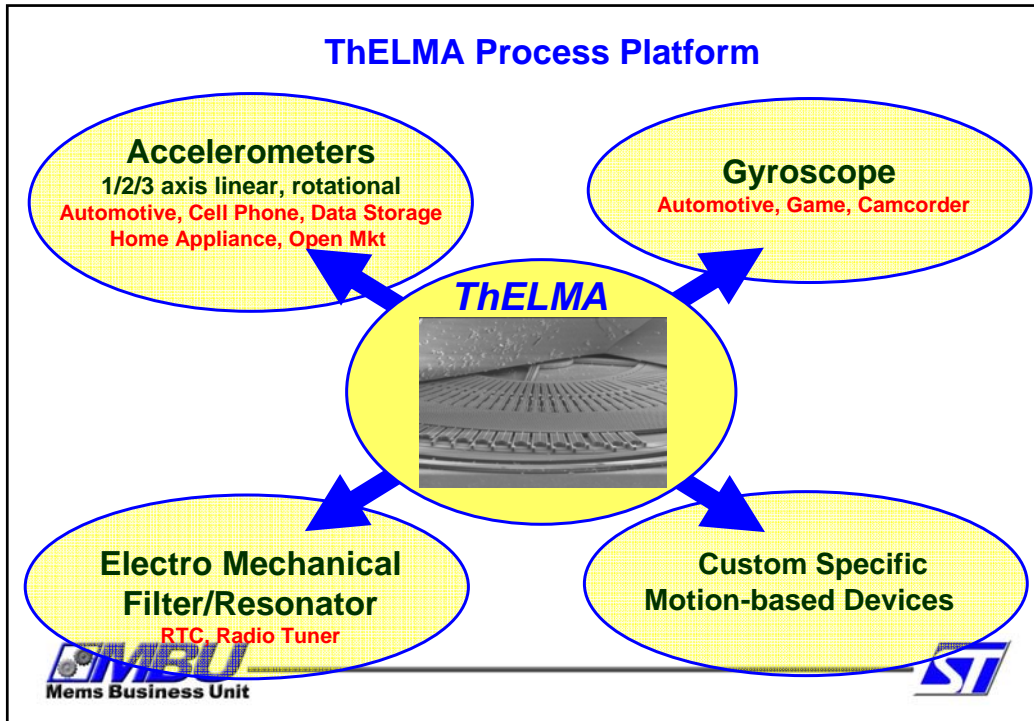
Thelma

- **Epitaxial Poly Growth**
 - From few μm up to 50 μm
- **Mechanical Polishing**
 - Smooth Surface - Stress Reduction
- **Deep Silicon Etching**
 - High Aspect Ratio – Vertical Sidewall
 - Low Cross-Talk – High Resolution
- **HF Dry Etching**
 - No Stiction – Free Structures

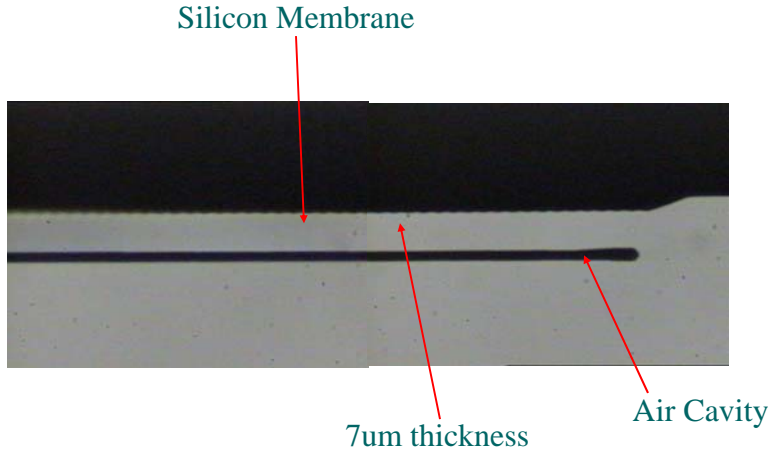
Wafer Level Protection with Silicon Cap

- **Wafer to Wafer Bonding**
 - Structure Protection in wafer sawing
 - Wafer scale Package

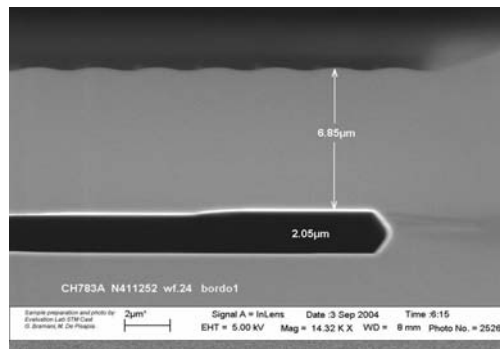
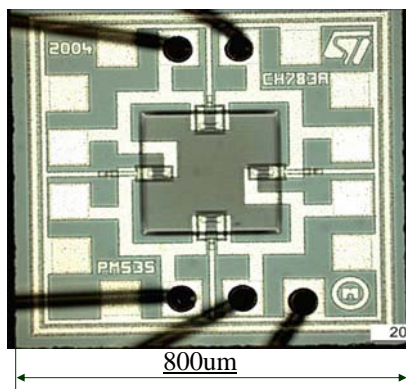




Venezia Process platform



Micromachining Process for Pressure and Force Sensors

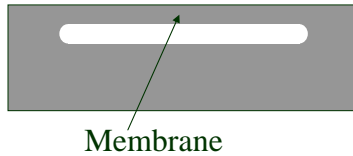


ST solution advantages

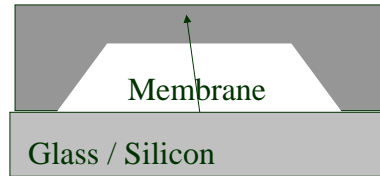
- Very small footprint and thickness
- Vertical Stoppers to avoid breakage
- Hermetic cavity; no need of wafer bonding
- Higher Sensitivity to Pressure
- Lower Sensitivity to Spurious Accelerations

LOW COST

ST Technology

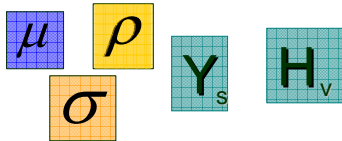


Current Technology



MACRO to MICRO: a big transition

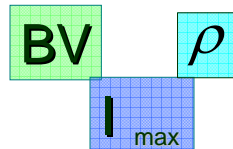
MECHANICAL PROPERTIES:



THERMAL PROPERTIES :



ELECTRICAL PROPERTIES :



CHEMICAL PROPERTIES :

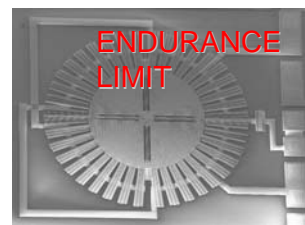
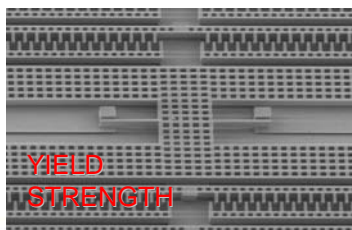
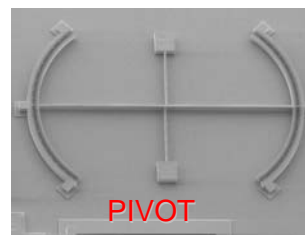
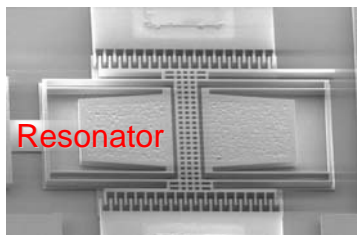


HOW TO OBTAIN THESE?

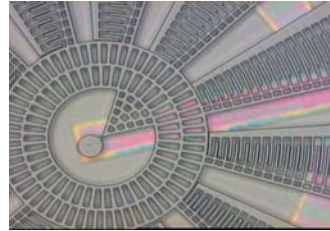
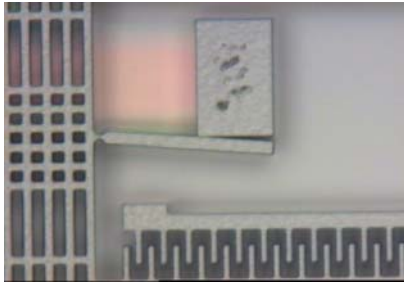
MEMS Reliability Approach

- **Basic studies on dedicated test structures**
 - Material characterization
 - Key failure mechanisms investigation
 - Design rules definition
- **Validation tests on sub-parts**
 - Technology oriented validation
 - Specific critical issues early investigation
- **Qualification exercise on final MEMS device**
 - Whole system design validation
 - Assembly stresses compatibility
 - Real field application simulation

Test Structures for Wafer Level Reliability Program



Yield Strength, Young Module Measurements



Quality Test for High Vacuum level

Quality factor test to ensure high vacuum level for vibrating MEMS devices.

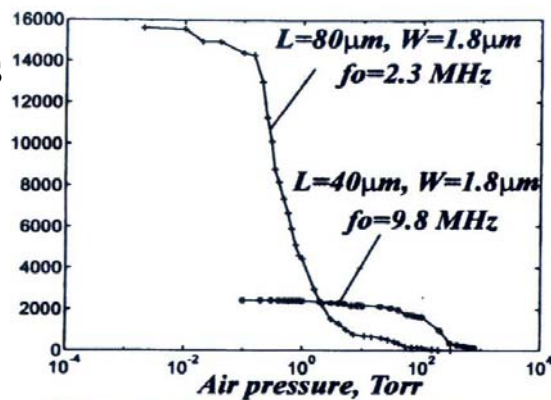
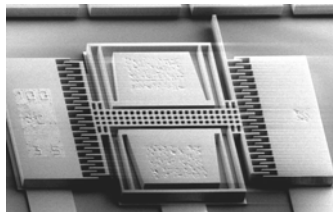


Figure 5. Plot of quality factor versus operating air pressure.

Conclusions

- **MEMS Process Standardization inside a company** is a key step for the commercial success of MEMS
- ST is pursuing two processes platforms: **Thelma and Venezia** for different micro-machined product families. A big effort is currently on-going to port other MEMS design in these industrialized processes.
- Reliability assessment procedures are very **specific**. Although Silicon is the base material the **failure mechanisms** are new and depend on the market segment, application and product
- **Reliability** assessment procedure must be derived from other industries and implemented at **wafer level**.
- **MEMS Foundry is an oxymoron**: a common process platform doesn't exist. MEMS are different from CMOS where company alliances exist and work in the same fab.
- **Ideal Process doesn't exist**: Each company will use its own preferred and available manufacturing process to run the production at lowest possible cost to compete successfully on the market at highest quality standards.



THANK YOU

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